



Application of Atomic Layer Deposited Microchannel Plates to Fast Timing Imaging Detectors

Oswald Siegmund, Jason McPhate, John Vallerga Space Sciences Laboratory, U.C. Berkeley Henry Frisch, University of Chicago Jeff Elam, Anil Mane, Robert Wagner Argonne National Laboratory Michael Minot, Chris Craven, INCOM Inc.

Borosilicate Substrate Atomic Layer Deposited Microchannel Plates

Micro-capillary arrays (Incom) with 10µm, 20 µm or 40µm pores (8° bias) made with borosilicate glass. L/d typically 60:1 but can be much larger. Open area ratios from 60% to 83%. These are made with hollow tubes, no etching is needed. Resistive and secondary emissive layers are applied (Argonne Lab, Arradiance) to allow these to function as MCP electron multipliers.



40µm pore borosilicate microcapillary MCP with 83% open area.

Pore distortions at multifiber boundaries, otherwise very uniform.

Photo of a 20 µm pore, 65% open area borosilicate microcapillary ALD MCP (20cm).

Photo of a 10 µm pore, 60% open area O. Siegmund, Workshop on Picosecond Sensors 3/12/14



ALD / Borosilicate Glass MCPs

Fabricated using hollow tube draw and stack technique Glass is inexpensive, low Z (no lead), and has a higher softening temperature (>700°C)

- Lower background, and low high energy particle cross section
- Deposition of high Temp opaque photocathodes like GaN
- Very large formats (>20cm) are possible

Functionalized using Atomic Layer Deposition (ALD)

- Semiconductor Resistive layer, tunable over wide range
- Amplifying layer (eg. Al_2O_3) with high secondary electron coeff.
- -Better lattice match to GaN, also good for conventional cathodes
- -Can be used on conventional MCPs and MCP substrates

Separates surface optimization from substrate optimization!

ALD-MCP Performance Tests, 33mm pairs

MCP pair, 20 μ m pores, 8° bias, 60:1 L/d, 0.7mm pair gap with 300V bias.

UV illuminated test results show similar gains to conventional MCPs, exponential gain dependence for low applied voltages, then saturation effects appear above gains of 10⁶. Pulse heights are reasonably normal for 60:1 L/d pairs. Background rates are low.



Pulse height amplitude distributions. 33mm MCP pair, 20µm pores, 8° bias, 60:1 L/d, 0.7mm pair gap with 300V bias. 3000 sec background.



3000 sec background, 0.0845 events $cm^{-2} sec^{-1}$ at 7 x 10⁶ gain, 1050v bias each MCP. Get same behavior for most of the current 20µm ALD MCPs.



ALD-MCP Gain and Pulse Amplitude





Pulse amplitude distributions for UV events 60:1 L/d, 60% OAR, MCP pair, 20µm pores 8° bias, 60:1 L/d, before and after 350°C bake. Image of 185nm UV light, <u>ALD MCP pair</u>, 20µm pores, 8° bias, 60% OAR, shows top MCP hex modulation and MCP hexagonal modulation from bottom MCP. 0.7mm pair gap with 300V bias.

MgO ALD on Conventional MCP "Z" Stack Conventional MCP "Z" stack with 10µm pores,

80:1 L/D, MgO coating on all MCPs.



Stack scrubs up in gain as expected from earlier data. Expect stabilization at ~0.05 C cm⁻². General background stays at typical values (~0.4 events cm⁻²). High secondary yield gives quite narrow PHDs even at comparatively low gain/applied voltages.

Conventional MCP – MgO ALD Coated

Conventional MCP with 6µm pores, 80:1 L/D, MgO coating



Slight gain drop (x2) at scrub initiation with significant gain increase thereafter Stabilizing after \sim 0.07 C cm⁻² extracted



Gain vs Charge Extraction Test, MCP Pairs

Top MCP – conventional 10µm 80:1 L/D – is the electron source

20µm pores, 60:1 L/D, Al₂O₃ coating

20µm pores, 60:1 L/D, MgO coating



MCP gain measured for bottom MCP



10µm Borosilicate MCP Substrate with ALD

33mm Borosilicate MCP with 10µm pores, 80:1 L/D, 8° bias



Single MCP Image (Phosphor) shows multifiber modulation (1100v MCP)



Single MCP gain is similar to conventional MCPs, gain saturation causes turnover.

33mm ALD-MCP Preconditioning Tests

Vacuum 350°C bakeout with RGA monitoring first, then UV flood low gain, high current extraction "burn in" (1 – 3μ A). Gain increases by x10 during bake. No rapid gain drop in scrub, gain-V curves remain very stable even after 1000 hours of N₂ exposure.



Gain curves of MCP pair (20 μ m pore, 60:1 L/d, 8° bias) at stages during preconditioning and nitrogen exposure (now up to 1000hr N₂ exposure, Jan 2014).



UV scrub of ALD MCP pair 164-163, (20 μ m pore, 60:1 L/d, 8° bias).



~30µm FWHM resolution @ 1.5x10⁶ gain, 4 MHz @85% livetime, conventional *MCPs. Siegmund et al, Amos Conf. Proceedings* 2011/2012, tubes built at PHOTONIS.

High Resolution Cross Strip Detector ALD MCP Test Scheme

100 mm square Cross Strip Anode microchannel plate photon counting detector with 128 x 128 strips/amplifiers. Developed for high spatial resolution, at lower gains, with higher count rates and longer lifetime, ~100ps time tagging.

< 20µm FWHM resolution @ 1.5x10⁶ gain, 4 MHz @85% livetime, 6µm pixels

Cross Delay Line Detectors

20cm MCP detector showing the cross delay line anode readout. 100ns end to end delay gives < 100µm spatial resolution.

20cm ALD 20µm pore MCP pair in detector

2.5cm 10µm MCP Z detector with SuperGen-II cathode and a cross delay line imaging readout.

(PHOTONIS)

Siegmund et al. Amos conference 2009

Quad-Timepix Detector in Planacon

Sealed tube "Planacon" with Quad-timepix readout, 55µm pixels, 25µm pore MCP pair, bialkali photocathode.

Readout < 20μ m FWHM resolution in centroid mode @ $5x10^4$ gain,

200MHz rates, and ~20ns event time tagging in 55µm pixel mode.

Vallerga et al, iworid 2013, in collaboration with CERN and Photonis-USA O. Siegmund, Workshop on Picosecond Sensors 3/12/14

Atomic Layer Deposited-MCP Summary

- Borosilicate Micro-capillary arrays offer a robust substrate for atomic layer deposited MCPs, and distortion/defect quality is still improving.
- Gain, imaging, and detection efficiency ~same as standard MCPs
- Background rates are low, <0.06 events cm⁻² sec⁻¹
- High temp vac bake for tube processing has very positive effects
 - Factor of >5x gain increase with MgO ALD SEY
 - Establishes very low MCP outgassing (borosilicate, ALD, MgO)
- Excellent MCP pair lifetest characteristics "burn-in"
 - Essentially no gain drop at the nominal gain over 7 C cm⁻²
 - Very stable to dry N₂ exposure thereafter
- ALD MgO/Al₂O₃ applied to normal MCPs help lifetime & gain
- ALD functionalized MCPs provide potential improvements in detector/ sealed tube/cathode lifetime and in reduction of the tube fabrication/processing turn around time.